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Advanced Fabrication Technologies for Micro/Nano Optics and Photonics XII

**Georg von Freymann
Winston V. Schoenfeld
Raymond C. Rumpf**
Editors

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Contents

v	<i>Authors</i>
vii	<i>Conference Committee</i>

NOVEL FABRICATION APPROACHES

10930 05	Refinements in membrane projection lithography: a route to fabrication of 3D metamaterials (Invited Paper) [10930-4]
----------	---

LARGE AREA FABRICATION

10930 0C	Inkjet printing of microlens arrays on large, lithographic structured substrates (Best Paper Award) [10930-11]
----------	---

APPLICATIONS FOR DLW

10930 0E	Immersion of nanodiamonds into three-dimensional direct-laser-written waveguides [10930-13]
10930 0G	Characterization of latent three-dimensional exposure patterns in photoresists [10930-15]
10930 0H	Additive manufacturing of titanium dioxide for dielectric photonic crystals [10930-16]

PHASE MASKS, PHANTOMS, AND STANDARDS

10930 0L	Laser-microfabrication with accurate positioning and metrological traceability [10930-20]
----------	--

NEW TECHNOLOGIES IN DLW: JOINT SESSION WITH 10909 AND 10930

10930 0V	Stitchless 3D printing of free-form functional mesoscale structures with resolution on-demand [10930-31]
10930 0W	Super-fine inkjet process for alignment-free integration of non-transparent structures into 3D-printed micro-optics (Best Student Paper Award) [10930-32]

HIGH-THROUGHPUT FABRICATION USING A DMD OR OTHER SLM DEVICE: JOINT SESSION WITH 10930 AND 10932

10930 0Z **Measurement and use of the refractive index distribution in optical elements created by additive manufacturing [10930-35]**

ADDITIVE MANUFACTURING USING DMD OR OTHER SLM DEVICE: JOINT SESSION WITH 10930 AND 10932

10930 11 **Holographic fabrication of graded photonic super-crystals through pixel-by-pixel phase coding of laser beams in a spatial light modulator [10930-37]**

POSTER SESSION

10930 12 **Towards inverse design of biomimetic nanostructures exhibiting composite structural coloration [10930-28]**

10930 13 **Nano-fabrication and characterization of non-uniform surface relief gratings in azobenzene molecular glass films [10930-38]**

10930 15 **Comparative study between wet and dry etching of silicon for microchannels fabrication [10930-40]**

10930 17 **A combined laser scanning and DLW tool for measuring and fabrication tasks with NPMM [10930-42]**

10930 1B **Demonstration of alignment error-free patterning of tapered waveguide using fixed beam moving stage e-beam lithography [10930-46]**

10930 1C **Are photonic nanojets achromatic? [10930-47]**

Authors

Numbers in the index correspond to the last two digits of the seven-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first five digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Baravykas, Tomas, 0V	Sinzinger, Stefan, 17
Barea, L. A. M., 15	Swanson, Nicholas, 13
Beckert, Erik, 0C	Symeonidis, Michail, 1C
Bove, V. Michael, 12	Thiele, Simon, 0W
Burckel, D. Bruce, 05	Toulouse, Andrea, 0W
Cirino, G. A., 15	Verdonck, P., 15
Dannberg, Peter, 0C	von Freymann, Georg, 0E
Datta, Bianca C., 12	von Zuben, A., 15
Diniz, J. A., 15	Vyatskikh, Andrey, 0H
Edwards, Bryce, 0H	Weidenfeller, Laura, 0L, 17
Frateschi, N. C., 15	Widera, Artur, 0E
Gadišauskas, Tomas, 0V	Yulianto, Edy, 0G
Gerhardt, Uwe, 17	
Giessen, Harald, 0W	
Greer, Julia R., 0H	
Gutsche, Jonas, 0E	
Hassan, Safaa, 11	
Heinrich, A., 0Z	
Herkommer, Alois M., 0W	
Hofmann, Martin, 0L	
Hurley, Noah, 11	
Jolly, Sundeep K., 12	
Jonušauskas, Linas, 0V	
Kemper, Falk, 0C	
Kim, Myun-Sik, 1C	
Kirchner, Johannes, 0L, 17	
Kühnel, Michael, 0L, 17	
Landowski, Alexander, 0E	
Lin, Yuankun, 11	
Lowell, David, 11	
Mackevičiūtė, Dovilė, 0V	
Mansano, R. D., 15	
Manske, Eberhard, 0L, 17	
Mastylo, Rostyslav, 17	
Mere, Viphretuo, 1B	
Mizeikis, Vygantas, 0G	
Musick, Katherine M., 05	
Ng, Ryan C., 0H	
Purlys, Vytautas, 0G, 0V	
Rangelow, Ivo, 0L	
Rank, M., 0Z	
Reif, Maximilian, 0C	
Reinhardt, Carsten, 0L	
Sabat, Ribai Georges, 13	
Sale, Oliver, 11	
Sauva, Sophie, 0C	
Scharf, Toralf, 1C	
Schreiber, Peter, 0C	
Selvaraja, Shankar Kumar, 1B	

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- 1 Opto-electronic Nano-devices
Georg von Freymann, Technische Universität Kaiserslautern (Germany)
- 2 Novel Fabrication Approaches
Debashis Chanda, University of Central Florida (United States)
- 3 Large Area Fabrication
Keith A. Brown, Boston University (United States)
- 4 Applications for DLW
Anant Agrawal, U.S. Food and Drug Administration (United States)
- 5 Phase Masks, Phantoms, and Standards
Georg von Freymann, Technische Universität Kaiserslautern (Germany)
- 6 Curved-space and Topological Photonics
Yoav Shechtman, Technion-Israel Institute of Technology (Israel)
- 7 Biomimetic Structural Color
Rivka Bekenstein, Technion-Israel Institute of Technology (Israel)
- 8 New Technologies in DLW: Joint Session with 10909 and 10930
Bo Gu, Bos Photonics (United States)
- 9 Novel Materials for DLW: Joint Session with 10909 and 10930
Harald Giessen, Universität Stuttgart (Germany)
- 10 High-throughput Fabrication using a DMD or other SLM Device: Joint Session with 10930 and 10932
Alfred Jacobsen, Visitech Engineering GmbH (Germany)
- 11 Additive Manufacturing using DMD or other SLM Device: Joint Session with 10930 and 10932
Bor-Kai Hsiung, University of California, San Diego (United States)